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Polymer microlens replication by Nanoimprint Lithography using proton beam fabricated Ni stamp

R.K. Dutta *, J.A. van Kan, A.A. Bettiol, F. Watt

Centre for Ion Beam Applications, Physics Department, National University of Singapore, Lower Kent Ridge Road, Singapore 117542, Singapore

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Abstract

It is essential to have a simplified and a rapid method for fabricating micro/nano structures in different kinds of polymeric materials. Though it is possible to fabricate arrays of microlens directly by P beam writing (PBW), it is restricted to a few types of resist materials. Therefore we have fabricated a Ni electroplated metallic stamp comprising of arrays of inverse/negative features of microlenses. The metallic stamp of about 500 μm thick is made on a silicon wafer coated with 10 μm thick polymethylglutarimide (PMGI) resist and the desired structures are written by PBW followed by thermal reflow and Ni electroplating. An array of microlenses is imprinted on a polycarbonate (PC) substrate by the Nanoimprint Lithography (NIL) technique and the replicated microlenses featuring various numerical apertures, diameters and pitches are characterized.

Keywords: Proton beam writing; PMGI resist; Electroplating; Nanoimprinting Lithography; Microlens array

1. Introduction

Microlenses and microlens array are finding applications mainly in the domain of optical microsystems, e.g. optical trapping [1], optical interconnects [2], biomedical instruments [3], optical data storage and optical communications [4]. Such a wide range of potential applications of these microphotonic devices have attracted a lot of different types of fabrication techniques. The fabrication of 3D lenses and array of microlenses are attempted using different types of micromachining techniques, for example: reflow of photoresist [5], LIGA [6], e-beam writing [7], polymer surface controlled microlens [8], eximer laser [9], focused ion beam – milling and deposition of SiO_2 [10], MeV proton deep lithography [11]. Each of these fabrication techniques has its own advantages and disadvantages, mainly with respect to physical type, quality of the microlenses and fabrication time.

In this regard, proton beam writing (PBW) technique, which is a direct write method, has been shown to be an effective one in constructing such microlens array [12]. Inspite of several positive features about fabrication by of PBW [13], it is comparatively a slow process. In order to have a large scale production of such microstructures, the following criteria needs to be fulfilled – (a) high through-put, (b) cost effective and (c) ability to fabricate a high quality metallic stamp for fast replication/prototyping.

In this paper, we report a method for fast prototyping of microlens array with a combination of PBW and Nanoimprint Lithography (NIL) technique. For this purpose a metallic stamp is fabricated by electroplating on a resist after creating suitable microlens features by PBW. The focal lengths of the prototyped microlenses are optically characterized.

2. Materials and methods

The process for metallic stamp fabrication using PBW has been extensively discussed earlier [14]. Briefly, a

* Corresponding author. Present address: Department of Chemistry, Indian Institute of Technology Roorkee, Roorkee 247667, India. Tel.: +91 1332 285280; fax: +91 1332 273560.
E-mail address: duttafcy@iitr.ernet.in (R.K. Dutta).

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conductive seed layers of Cr (20 nm) and Au (100 nm) were coated on a clean Si wafer followed by spin coating of 10 μm of PMGI positive resist. A suitable microlens array of various diameters and pitches (e.g. 80 μm, 100 μm, 120 μm and 150 μm) were patterned using P-beam writing facility at National University of Singapore [15].

A schematic flow chart of the above procedure is shown in Fig. 1. A 2 MeV proton beam focused to a spot size of 1 μm × 1 μm, was scanned magnetically over an area of 400 μm × 400 μm. The scanning was done in such a manner that array of desired circular features were unexposed. Such a patterned resist was developed in a mixture of 1-methoxy-2-propanol-acetate : ethanolamine : de-ionised water at a volume ratio of 60:20:5:15. This gave rise to pillar like cylindrical resist, which was heated above glass transition temperature, at 290 °C for 30 min. The resist melted and due to surface tension these array of cylindrical resist took a shape of spherical microlens array. A thin layer of second metallization, i.e. Ti, was coated on top surface which acted as a cathode base for metallic electroplating. The metallic stamp was delaminated from polymer layer by immersing in toluene. This metallic stamp with a base of 500 μm thickness was used for Nanoimprint Lithography (NIL). The surface of the stamp featuring structures for replicating microlens array required cleaning by diluted hydrochloric acid and rinsed with isopropyl alcohol.

For NIL prototyping, the metallic stamp was hot embossed against 500 μm polycarbonate (PC) sheet (refractive index of 1.587) for 30 s at 150 °C and 30 bar pressure in a Nanoimprinter. In this method, array of spherical microlenses and different dimensions of cylindrical lenses were replicated on PC sheet.

3. Results

A representative replica of an array of microlens of 150 μm diameter is shown in Fig. 2(a). The detailed feature of a microlens from an array of 150 μm microlens is a representation of the quality of the fabricated microlenses (shown in Fig. 2(b)). Further, 1D line profiling of these microlenses shows their nature of curvature and surface smoothness. The profilometer measurements were the experimental evidences of the diameter and height of the fabricated microlenses (Fig. 3). The heights of replicated microlenses were also measured from optical microscopy and were found to be in good agreement with the coated resist thickness (±1 μm) and to that of the profilometer measurements. A visual inspection in a microscope with white light illumination showed: (a) focal plane of a

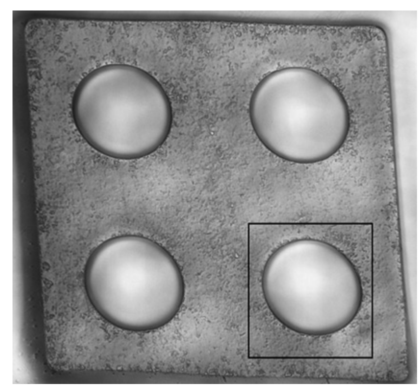

Fig. 2(a). Array of microlens of diameter 150 μm replicated by Nanoimprint Lithography on polycarbonate.

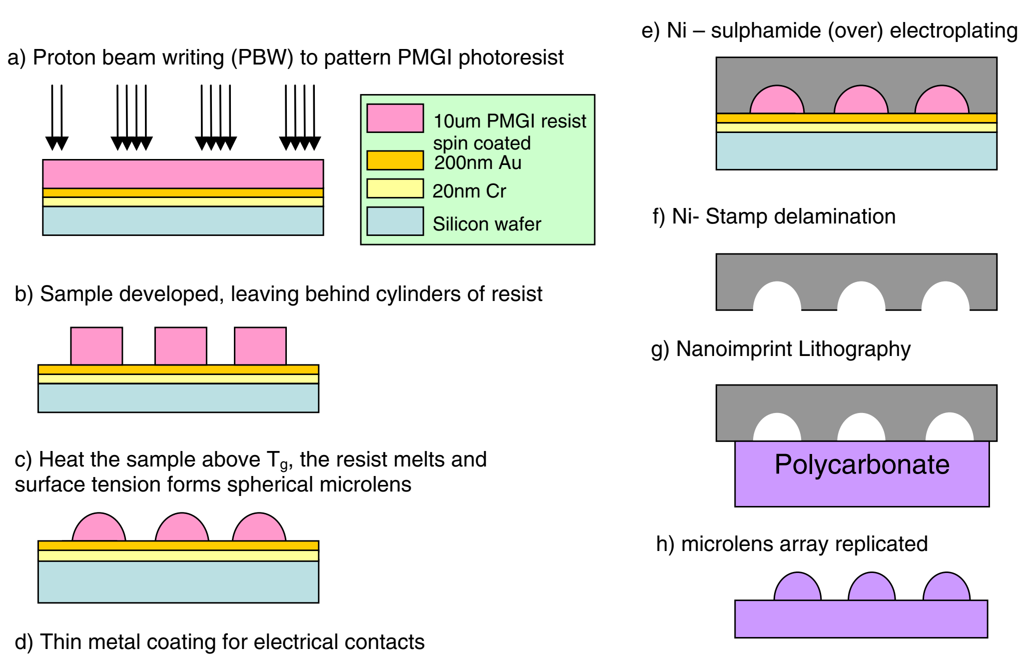

Fig. 1. A schematic flow chart for replicating microlens array in polycarbonate (PC). This includes patterning of resist by P beam writing, developing the patterned resist, reflow by heating, electroplating of Ni to make Ni stamp and finally Nanoimprinting Lithography on PC.